

Title_Dr.

First_Name_Stanislav

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Date_of_Birth_05/05/1952

Address_Center for Semiconductor Components – CCS, UNICAMP, C.P. 6061, CEP 13083-870, Campinas, SP, Brazil

Position_ Researcher, Head of Nanotechnology Group

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Graduated in 1975, in Physics_ Quantum Electronics, from St.Petersburg Polytechnical University, Russia

PhD_awarded_05/1984, Plasma Physics, Institute of Physics and Technology, Russian Academy of Sciences, St.Petersburg

Current Academic_position_Researcher

Department_ Center for Semiconductor Components – CCS - UNICAMP

Field_of_specialisation_Micro and nanofabrication and characterization, carbon nanotubes, nanoparticles, CVD, thin films, focused ion beam, AFM, Raman, nanocontacting, electrical properties, plasmas for micro and nanofabrication

Subject_ Nanodevices

Present research: controlled synthesis and characterization of carbon nanotubes, graphens, mechanisms of CNTs nucleation and growth, nanotube based sensors, CVD and PE-CVD techniques for CNT growth, plasmas and FIB for nanofabrication

List_of_publications: over 55 papers in scientific journals, total more than 200 publications.

List of 10 selected publications:

1. VERISSIMO, C., AGUIAR, M. R., Moshkalev, S. A.

Formation of Catalyst Nanoparticles and Nucleation of Carbon Nanotubes in Chemical Vapor Deposition. Journal of Nanoscience and Nanotechnology. , v.9, p.4459 - 4466, 2009.

2. Gelamo, R.V., Rouxinol, F.P., VERISSIMO, C., Vaz, A.R., Bica de Moraes, M.A., MOSHKALEV, S.A.

Low-temperature gas and pressure sensor based on multi-wall carbon nanotubes decorated with Ti nanoparticles. Chemical Physics Letters , v.482, p.302 - 306, 2009.

3. Aguiar, Marina R., Verissimo, Carla, Ramos, Antonio C. S., MOSHKALEV, S.A., Swart, Jacobus W.

Synthesis of Carbon Nanotubes and Nanofibers by Thermal CVD on SiO₂ and Al₂O₃ Support Layers. Journal of Nanoscience and Nanotechnology. , v.9, p.4143 - 4150, 2009.

4. MOSHKALEV, S.A., LEON, J., VERISSIMO, C., VAZ, A. R., FLACKER, A., MORAES, M. B., SWART, J. W.

Controlled Deposition and Electrical Characterization of Multi-Wall Carbon Nanotubes. Journal of Nano Research. , v.3, p.25 - 32, 2008.

5. DALTRINI, A. M., MOSHKALEV, S.A., MORGAN, T. J., PIEJAK, R. B., GRAHAM, W. G.

Plasma power measurement and hysteresis in the E to H transition of an RF inductively coupled plasma system. Applied Physics Letters. , v.92, p.061504-1 - 061504-3, 2008.

6. VAZ, A. R., MACCHI, M., LEON, J., MOSHKALEV, S.A., SWART, J. W.

Platinum thin films deposited on silicon oxide by focused ion beam: characterization and application. Journal of Materials Science. , v.43, p.3429 - 3434, 2008.

7. BIASOTTO, C., DINIZ, J, DALTRINI, A, MOSHKALEV, S.A., MONTEIRO, M
Silicon nitride thin films deposited by electron cyclotron resonance plasma enhanced chemical vapor deposition for micromechanical system applications. *Thin Solid Films.* , v.516, p.7777 - 7782, 2008.
8. VERISSIMO, C., GOBBI, A., MOSHKALEV, S.A.
Synthesis of carbon nanotubes directly over TEM grids aiming the study of nucleation and growth mechanisms. *Applied Surface Science.* , v.254, p.3890 - 3895, 2008.
9. MOSHKALEV, S.A., VERISSIMO, C.
Nucleation and growth of carbon nanotubes in catalytic chemical vapor deposition. *Journal of Applied Physics.* , v.102, p.044303-1 - 044303-6, 2007.
10. VERISSIMO, C., MOSHKALEV, S.A., RAMOS, A. C., GONCALVES, J. L., ALVES, O. L., SWART, J. W.
Different Carbon Nanostructured Materials Obtained in Catalytic Chemical Vapor Deposition. *Journal of the Brazilian Chemical Society.* , v.17, p.1124 - 1132, 2006.